

to copper contamination, and storing a silicon wafer in the prepared water or a chemical solution.

Sub B2 4. (Amended) A method of storing a silicon wafer in water, [wherein] comprising the steps of preparing storage water containing Cu at a concentration of 0.01 ppb or less [is used], and storing a silicon wafer in the prepared storage water.

5. (Amended) A method of storing a silicon wafer in water according to Claim 4, wherein the step of preparing storage water includes using storage water containing a surfactant [is used].

6. (Amended) A method of storing a silicon wafer in water according to Claim 4, wherein the step of storing a silicon wafer includes providing a silicon wafer [to be stored has] having a hydrophobic surface.

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Sub B3 7. (Amended) A method of storing a silicon wafer in water according to Claim 5, wherein the step of storing a silicon wafer includes providing a silicon wafer [to be stored has] having a hydrophobic surface.

8. (Amended) A method of storing a silicon wafer in water according to Claim 4, wherein the step of storing the silicon wafer comprises storing the silicon wafer [is stored] immediately after polishing.

Sub B4 9. (Amended) A method of storing a silicon wafer in water according to Claim 5, wherein the step of storing the silicon wafer comprises storing the silicon wafer [is stored] immediately after polishing.

10. (Amended) A method of storing a silicon wafer in water according to Claim 6, wherein the step of storing the silicon wafer comprises storing the silicon wafer [is stored] immediately after polishing.

Sub 03 11. (Amended) A method of storing a silicon wafer in water according to Claim 7, wherein the step of storing the silicon wafer comprises storing the silicon wafer [is stored] immediately after polishing.

A 1 12. (Amended) A method of storing a silicon wafer in a storage solution, comprising the steps of preparing [wherein the storage solution is mainly formed of water or a chemical solution [to which] containing a chelating agent [is added], and storing a silicon wafer in the prepared water or chemical solution.

13. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 12, wherein the step of storing a silicon wafer includes providing a silicon wafer [to be stored has] having a hydrophobic surface.

14. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 12, wherein the step of preparing water or a chemical solution includes providing [the chemical solution to which the chelating agent is added is] an alkaline solution as the chemical solution containing a chelating agent.

15. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 13, wherein the step of preparing water or a chemical solution

includes providing [the chemical solution to which the chelating agent is added is]
an alkaline solution as the chemical solution containing a chelating agent.

16. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 12, wherein the step of preparing water or a chemical solution includes the step of adding a surfactant [is added] to the water or chemical solution [to which the chelating agent is added] containing a chelating agent.

17. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 13, wherein the step of preparing water or a chemical solution includes the step of adding a surfactant [is added] to the water or chemical solution [to which the chelating agent is added] containing a chelating agent.

A 18. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 14, wherein the step of preparing water or a chemical solution includes the step of adding a surfactant [is added] to the water or chemical solution [to which the chelating agent is added] containing a chelating agent.

19. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 12, wherein the step of preparing water or a chemical solution includes preparing water or a chemical solution containing a chelating agent [has] having a chelate compound production performance not lower than that of NTA.

20. (Amended) A method of storing a silicon wafer in a storage solution according to Claim 12, wherein the step of preparing water or a chemical solution